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**The Science and Technology
of Vapor Phase Processing
and Modification of Surfaces**



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THE SCIENCE AND TECHNOLOGY OF VAPOR PHASE PROCESSING AND MODIFICATION OF SURFACES

443 Introduction Haitao Ye, Chengming Li, Sarah Hainsworth

ARTICLES

444–453 Tribocorrosion behavior of Ca–P MAO coatings on Ti6Al4V alloy at various applied voltages You Zuo, Tianlu Li, Xinyun Jiang, Minbao Wu, You Zhang, Fei Chen

454–461 Transport characteristics of type II Weyl semimetal MoTe₂ thin films grown by chemical vapor deposition Niraj Bhattarai, Andrew W. Forbes, Rajendra P. Dulal, Ian L. Pegg, John Philip

462–472 Fast smoothing on diamond surface by inductively coupled plasma reactive ion etching Yuting Zheng, Jinlong Liu, Ruoying Zhang, Aude Cumont, Jue Wang, Junjun Wei, Chengming Li, Haitao Ye

473–480 Preparation and characterization of heat-insulating Ag/TiO₂ composite membranes based on magnetron sputtering technology Tingting Zhuo, Shan He, Binjie Xin, Zhuoming Chen, Xiaoxia Liu, Mingyu Zhuang

481–490 A diffusion approach for plasma synthesis of superhard tantalum borides Aaditya Rau, Kallol Chakrabarty, William Gullion, Paul A. Baker, Ilias Bikmukhametov, Richard L. Martens, Gregory B. Thompson, Shane A. Catledge

491–499 The effect of MoW interlayer thickness on diamond growth on steel substrates Vojtěch Kunderát, Ruoying Zhang, Xiaoling Zhang, Kevin Cooke, Hailin Sun, John Sullivan, Haitao Ye

500–507 Improved oxidation resistance of CoNiCrAlTaHfY/Co coating on C/C composites by vapor phase surface alloying Qi Guo, Tianxu Meng, Wenqiang Ding, Wen Xi, Naiming Lin, Shengwang Yu, Xiaoping Liu

508–515 Enhancement of diamond seeding on aluminum nitride dielectric by electrostatic adsorption for GaN-on-diamond preparation Xin Jia, Jun-jun Wei, Yabo Huang, Siwu Shao, Kang An, Yuechan Kong, Lishu Wu, Zhina Qi, Jinlong Liu, Liangxian Chen, Chengming Li

516–526 A combined experimental and first-principle study on the effect of plasma surface Ta–W co-alloying on the oxidation behavior of γ-TiAl at 900 °C Dongbo Wei, Fengkun Li, Shuqin Li, Shiyuan Wang, Feng Ding, Hongxuan Liang, Yuqin Yan, Pingze Zhang

527–536 Effect of LPHT annealing on interface characteristics between HPHT Ib diamond substrates and homoepitaxial CVD diamond layers Xiaohua Zhu, Jinlong Liu, Siwu Shao, Yun Zhao, Juping Tu, Liangxian Chen, Junjun Wei, Chengming Li